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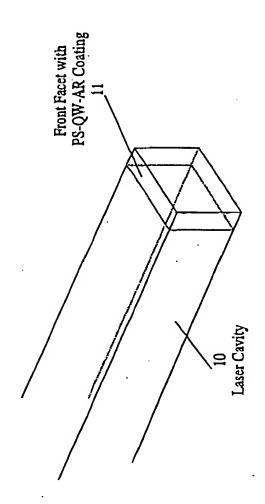
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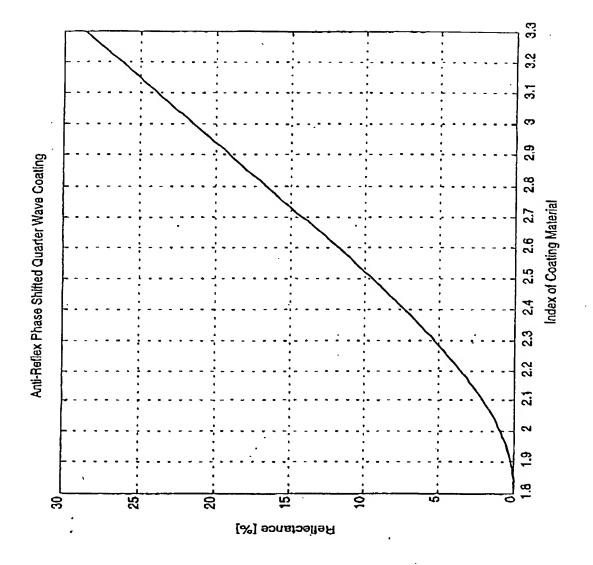
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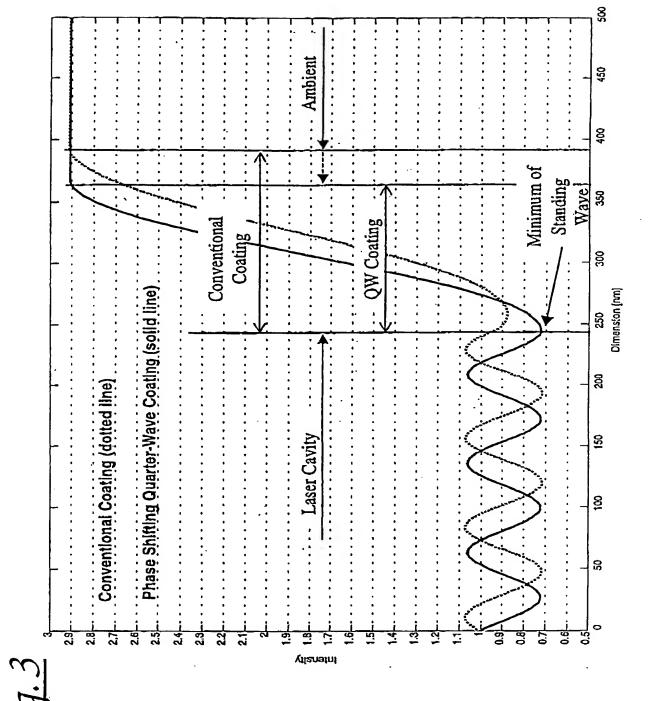
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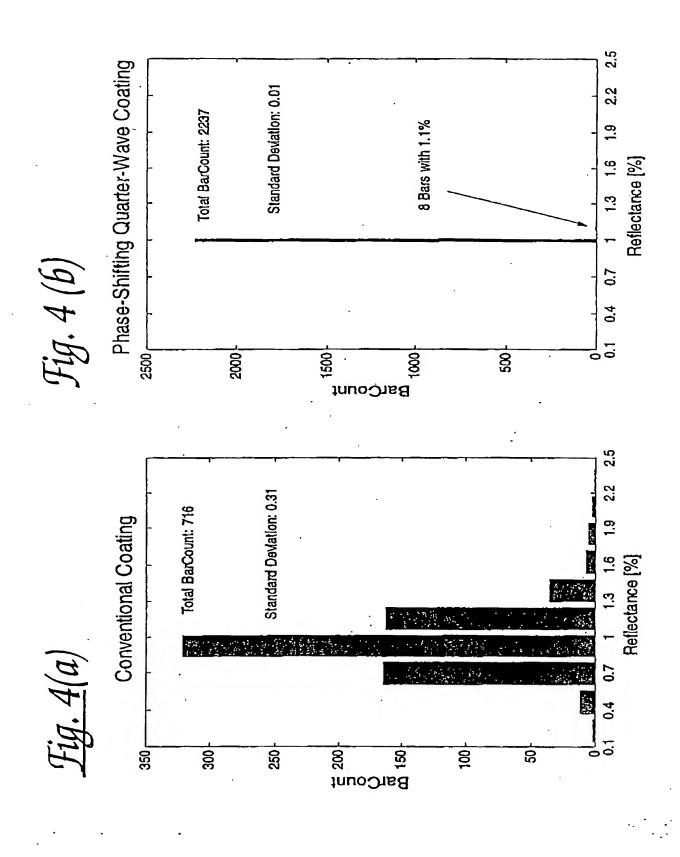
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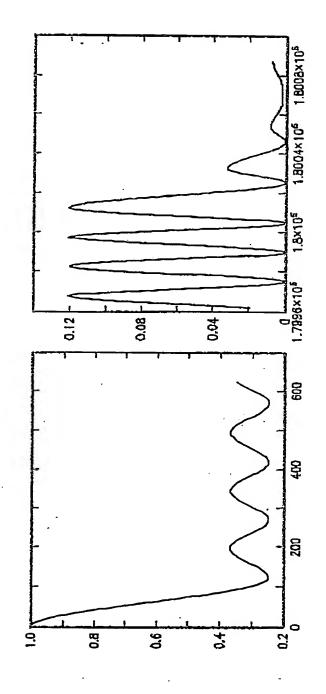
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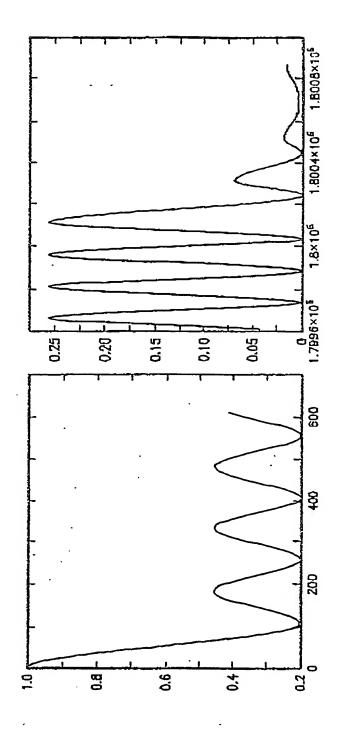




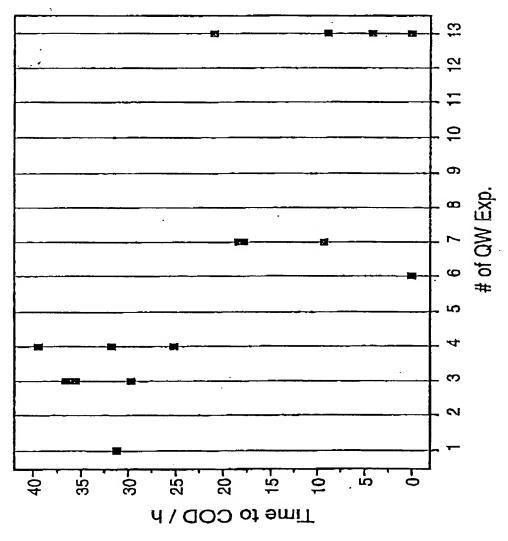




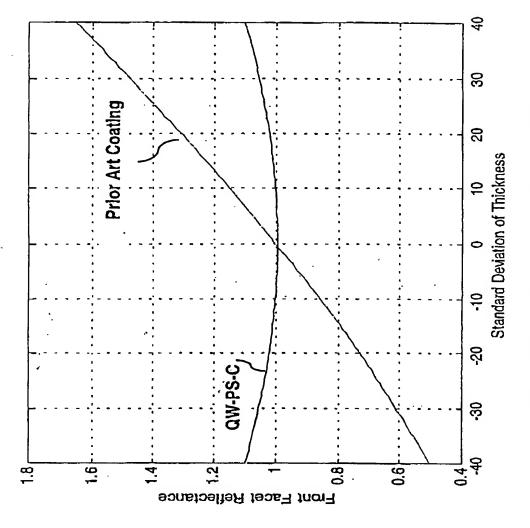
Phase Shifting Quarter Wave Coating with a 1 % Reflectance



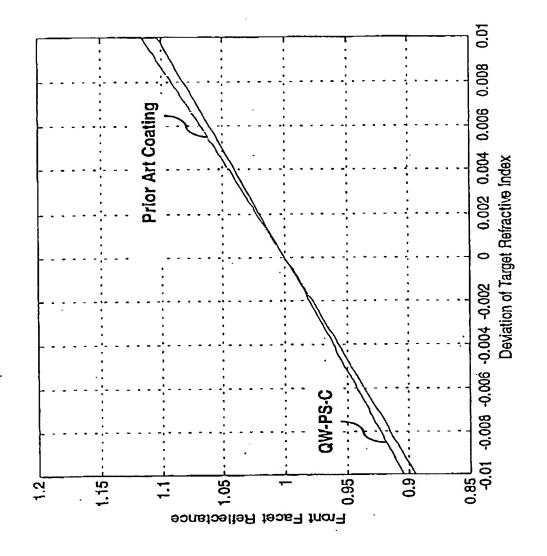
Phase Shifting Quarter Wave Coating with a 4 % Reflectance



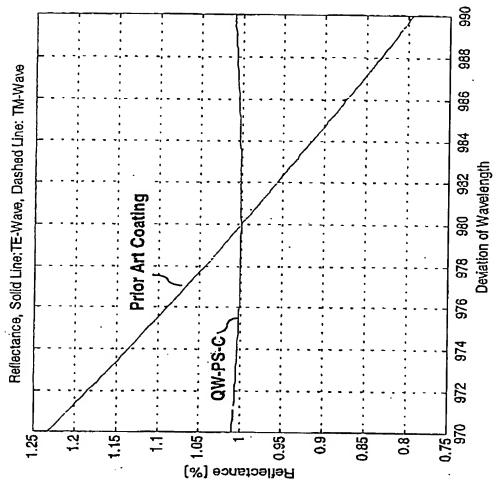
Time to COD vs. # of QW Exp



Dependence of reflectance on thickness variation



Dependence of Reflectance on index variation



Dependence of reflectance on wavelength variation

## Process parameters

Reflectivity	Reflectivity Index of refraction   Subst	Substrate Temperature   Pressure   Plasma Power   nitrogen flux	Pressure	Plasma Power	_	ammonia flux	silane flux(*)
R	u	T <sub>S</sub> (°C)	P (Torr)	L plasma (W) n	(sccm)	п ринај (sccm)	п (sінд (sccm)
0.05%	1.86	300	1.4	25	35	18	236
1%	2.01	300	1.4	25	35	13	403
4%	2.23	300	1.4	25	35	8.5	491
1%(**)	1.83	300	1.4	20	330	11.2	300

(\*) precursor gas of 2% SiH4 diluted in Helium (\*\*) conventional non- $\lambda/4$  coating

